cket No. A-67736-1/MSS/TJH Dorsey Matter No.: 463035-19

CERTIFIC NDER 37 C.F.R. 1.10

I hereby certify that this paper (along with any referred to as being attached or enclosed) is being deposited with the United States Postal Service with sufficient postage as First Class Mail in an envelope addressed Assistant Commissioner for Patents, Washington, D.C. 20231 on March 31, 2008.

Signed

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

*In re* application of:

SAVAGE et al.

09/767,659 Application No.

Filed:

January 22, 2001

For: Semiconductor Wafer Processing

System with Vertically-Stacked Process Chambers and Single-Axis

Dual Wafer Transfer System

Examiner:

FOX, Charles A.

Art Unit:

3652

Box AF **Assistant Commissioner for Patents** Washington, D.C. 20231

Sir:

ry 22, 200
Processing
y-Stacked
d Single-Axis
System

AMENDMENT AFTER FINAL

App
9,2003
Ction in Act December 31, 2002. This Amendment is responsive to the final Office Action Please amend the application as follows:

In the Claims:

Please amend claims 19 and 24 to read as shown:

19. (Amended) A method of semiconductor wafer processing comprising the steps of: providing a multi-chamber module including a plurality of vertically-stacked semiconductor wafer process chambers;

providing a loadlock chamber for each of the vertically-stacked semiconductor wafer process chambers, wherein each loadlock chamber having a transfer arm including an upper wafer shelf for carrying unprocessed wafers and a lower wafer shelf for carrying processed wafers, and a semiconductor wafer process chamber;